



UNIT-2 Transistors

Syllabus

Bipolar Junction Transistor: Transistor Construction, Operation, Amplification action. Common Base, Common Emitter, Common Collector Configuration

Field Effect Transistor: Construction and Characteristic of JFETs. Transfer Characteristic.

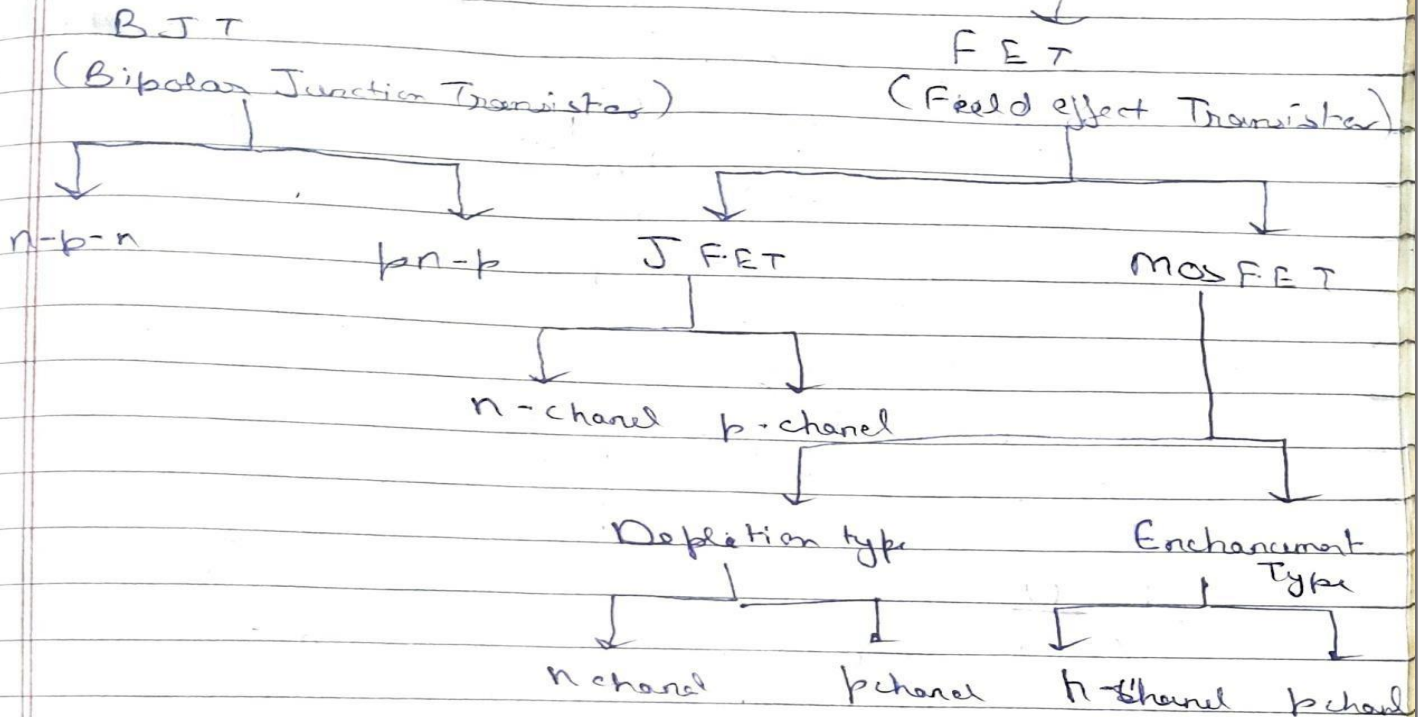
MOSFET (MOS)(Depletion and Enhancement) Type, Transfer Characteristic.



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Unit 2

Transistors



Transistor is a device which transfer applied signal from one type of resistor to other type. e.g. signal can be transferred from low resistor to high or from high resistor to low resistor

Transistor (Transfer + resistor)

Transistor is called bipolar device because its operation depends on the interaction of majority and minority carriers both.

Construction of Transistor (BJT)

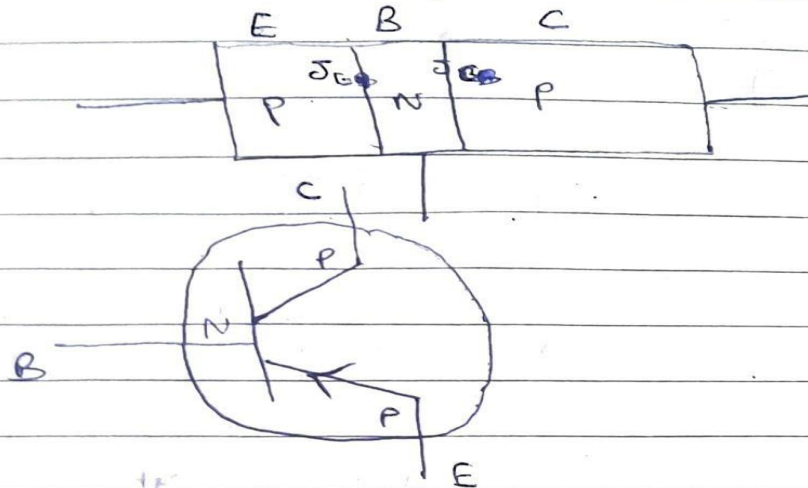
When in between two thick semiconductor a thin semiconductor is fused then arrangement is so formed is known as transistor

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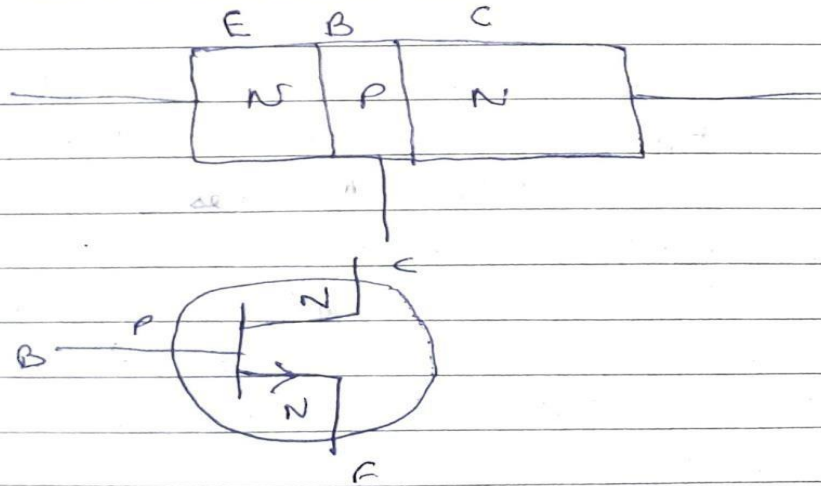
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There are two type of transistor:

- ① PNP Transistor: When in between two thick p type semiconductor a thin n type semiconductor is fused then the transistor so formed is known as PNP Transistor



- ② NPN Transistor: When in b/w two thick n type s/c a thin p type s/c is fused then the transistor so formed is known as NPN Transistor



There are three main regions of transistor:

- ① Emitter: The region from which holes or e^- are emitted it is of moderate in size and heavily doped



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② Base : The middle layer of the transistor is called called Base. It is very thin and lightly doped.

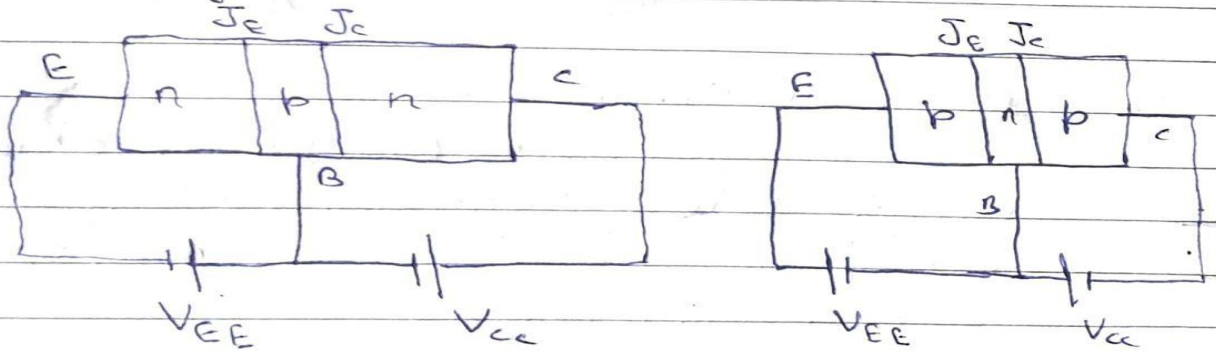
③ Collector : The region which collects the the holes or e^- emitted from emitter is called collectors. It is large in size and moderately doped..

Size $C > E > B$
dopping $E > C > B$

Mode of Operations

① Active Mode or region :-

In active region emitter-base junction (J_{E}) is forward biased and collector-base junction (J_{C}) is reverse biased. In this region transistor works as an amplifier

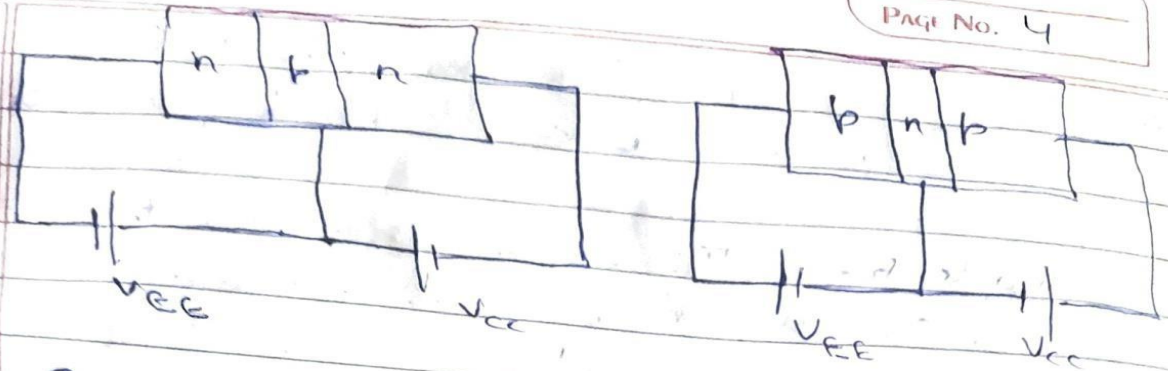


② Saturation region :-

In this region emitter-base junction (J_{E}) and collector base junction (J_{C}) are forward biased. In this region transistor works as a closed switch



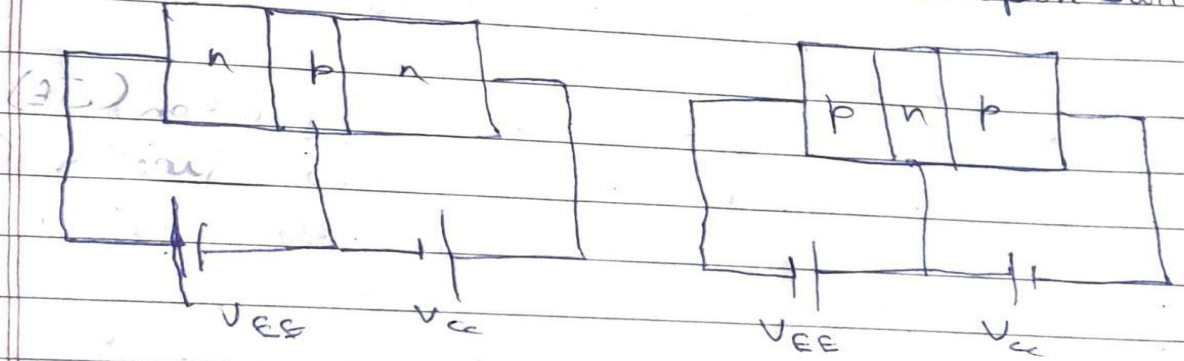
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③

Cut-off region:

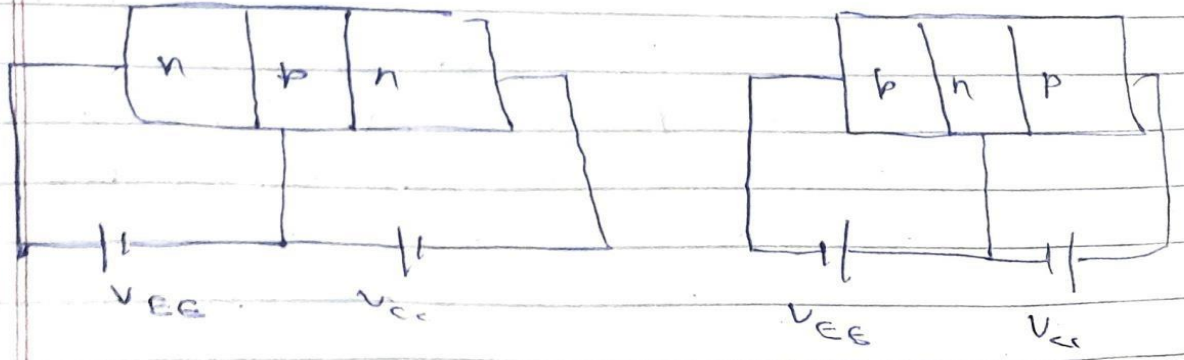
In this region emitter-base junction (J_E) and collector base junction (J_C) are reverse biased. In this region transistor work as a open switch.



④

Reverse Active mode:

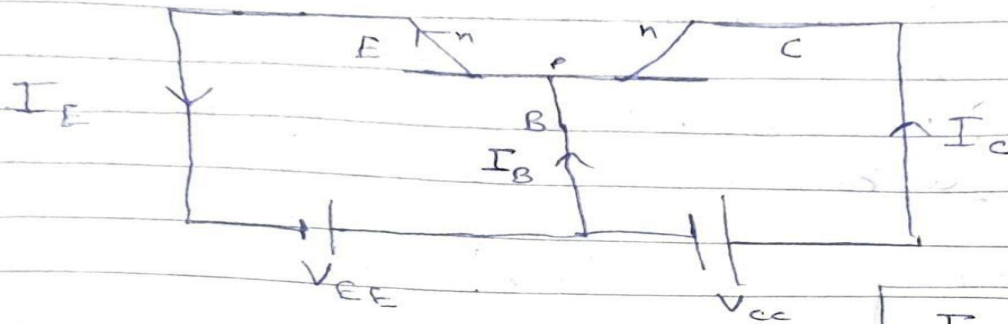
In this region emitter base junction (J_E) is reverse biased while collector base junction is forward biased. In this region transistor never operated because gain is negligible.



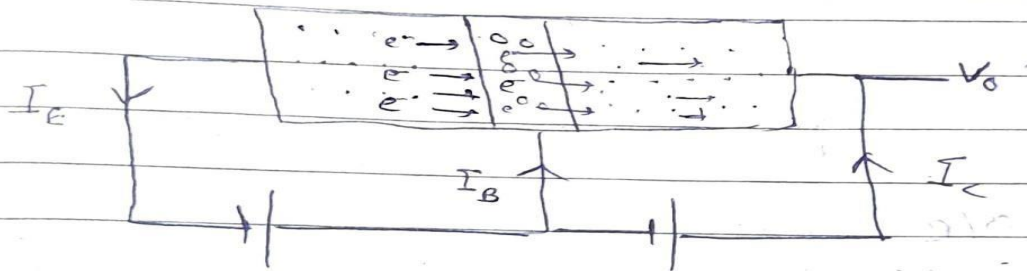


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Common base Configuration



$$I_E = I_B + I_C$$



e^- from the emitter region are repelled by -ve terminal of the battery V_{EE} giving the emitter current I_E . 5% of e^- get combined in the base with the holes giving the base current and remaining 95% will move to collector giving collector current.

→ Current gain :- It is a ratio of o/p current and i/p current.

$$\alpha = \frac{I_C}{I_E}$$

→ Voltage gain :-

$$A_V = \frac{I_C R_C}{I_E R_E} = \alpha \frac{R_C}{R_E}$$

→ Power gain :-

$$P_a = VI \Rightarrow \alpha \frac{R_C}{R_E} \times \frac{I_C}{I_E}$$

$$P_a = \alpha^2 \frac{R_C}{R_E}$$



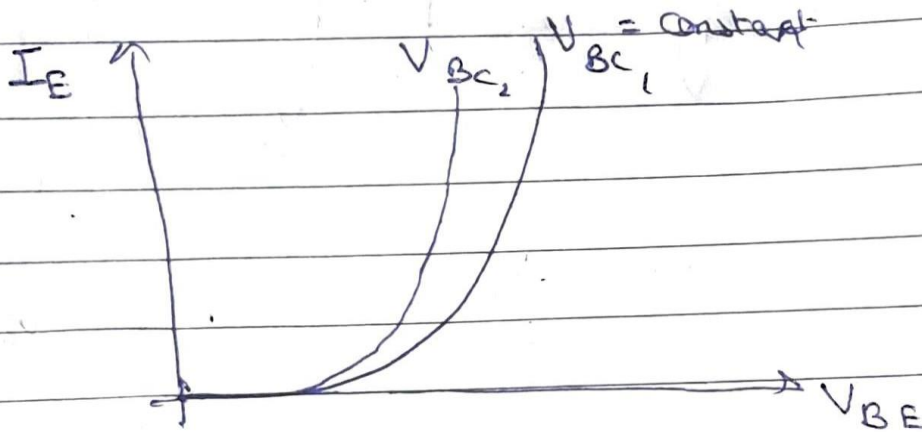
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I/P & O/P characteristics of CB configuration

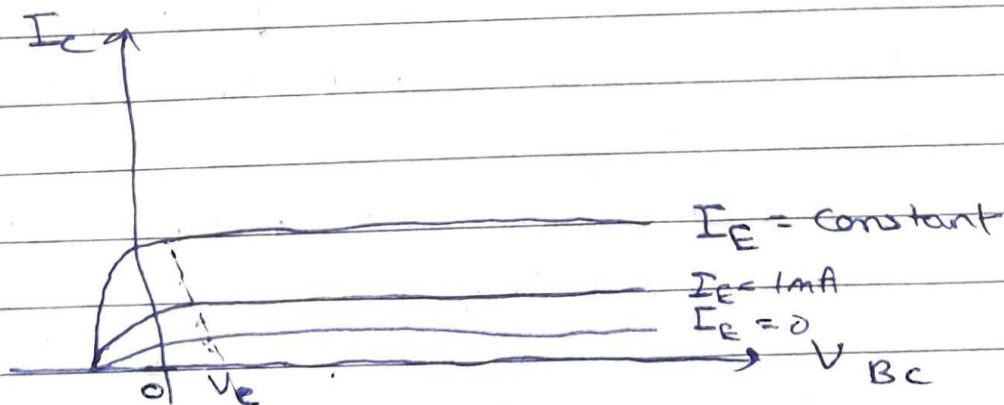
→ I/P characteristics :-

~~It is a curve b/w~~ The variation in the emitter current (I_E) with respect to change in base to emitter voltage (V_{BE}) at constant collector to base voltage V_{BC}



→ O/P characteristics :-

The variation in the collector current (I_C) with change in collector to base voltage V_{BC} at constant emitter current (I_E)

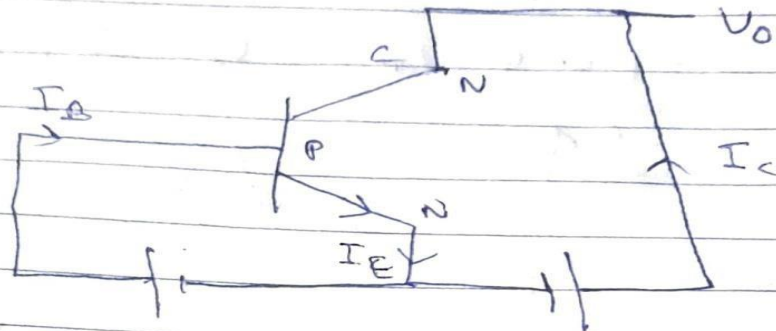


in which I_C becomes constant

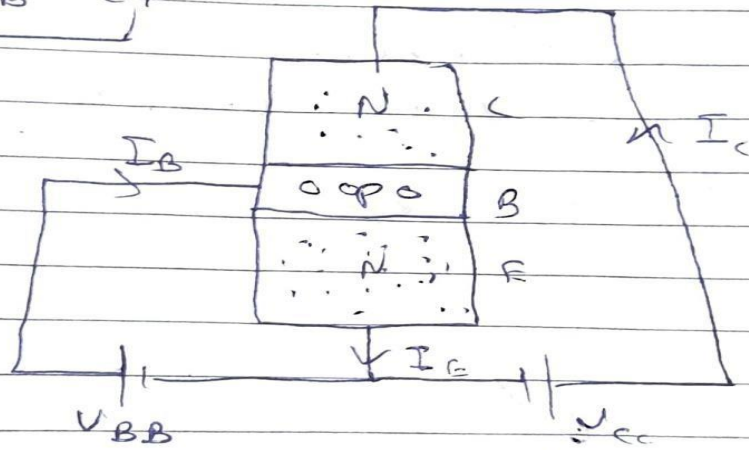


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Common Emitter configuration



$$I_E = I_B + I_C$$



The emitter e^- s are repelled by $-ve$ terminal of the battery V_{BB} giving emitter current (I_E). 5% of e^- get combined with holes in the base region giving the base current and remaining 95% will move to collector giving the collector current

→ Current gain

$$\beta = \frac{I_C}{I_B}$$

$$\text{Voltage gain} = \beta \frac{R_C}{R_B}$$

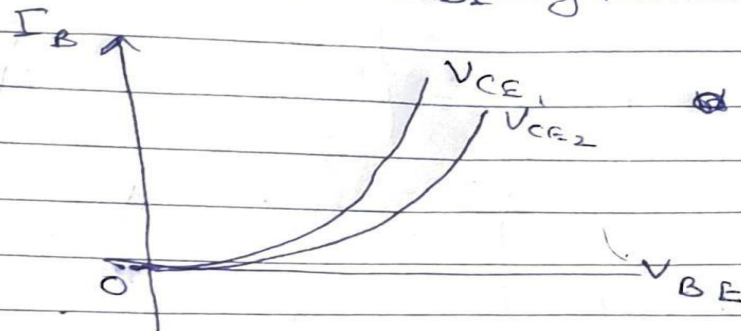
$$\text{Power gain} = \beta^2 \frac{R_C}{R_B}$$

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I/P o/p characteristics of CE configuration

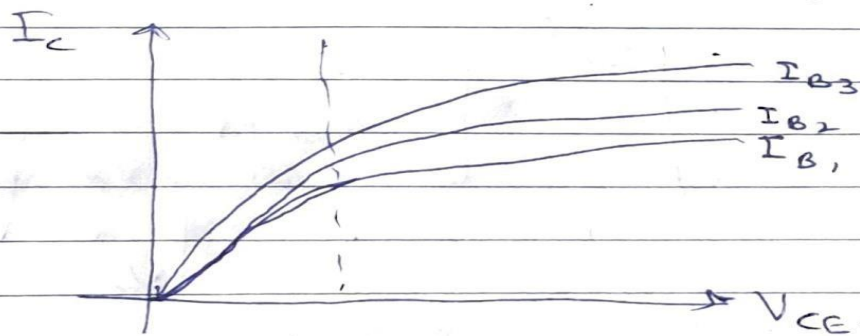
→ I/P characteristics :-

It is a plot of I_B and V_{BE} by maintaining V_{CE} ^{constant}

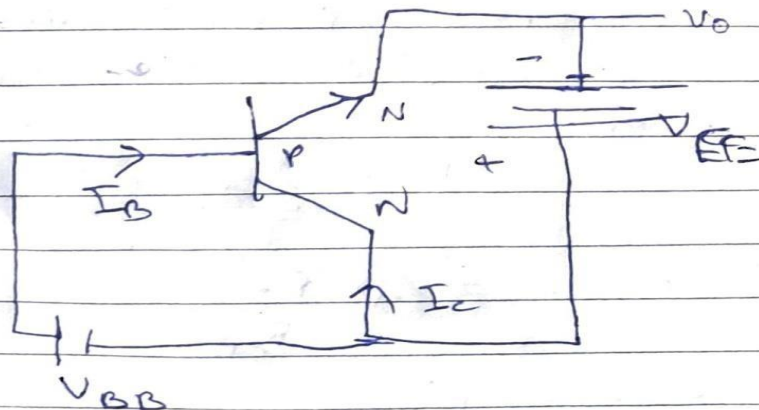


→ O/P characteristics :-

A plot of I_C and V_{CE} while maintaining I_B constant

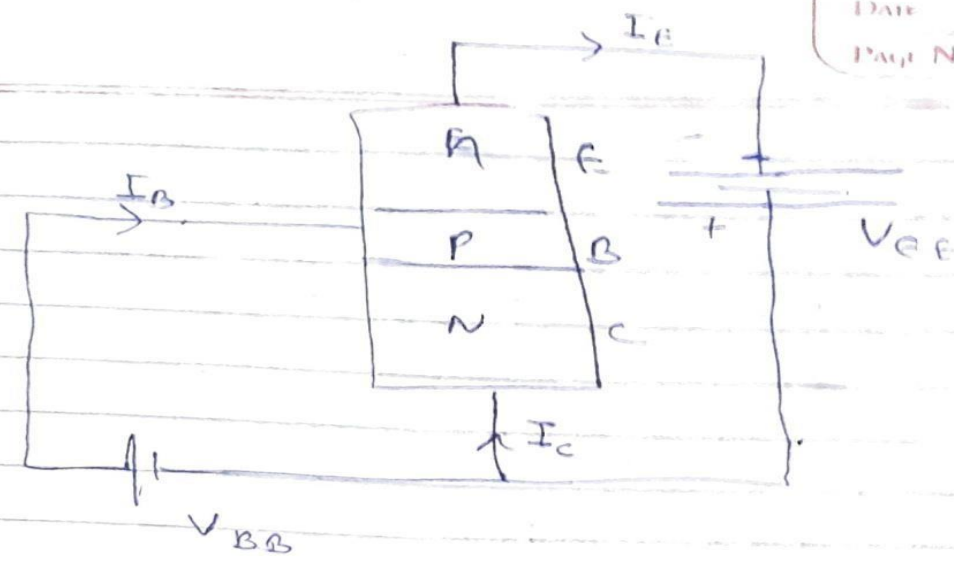


Common Collector Configuration





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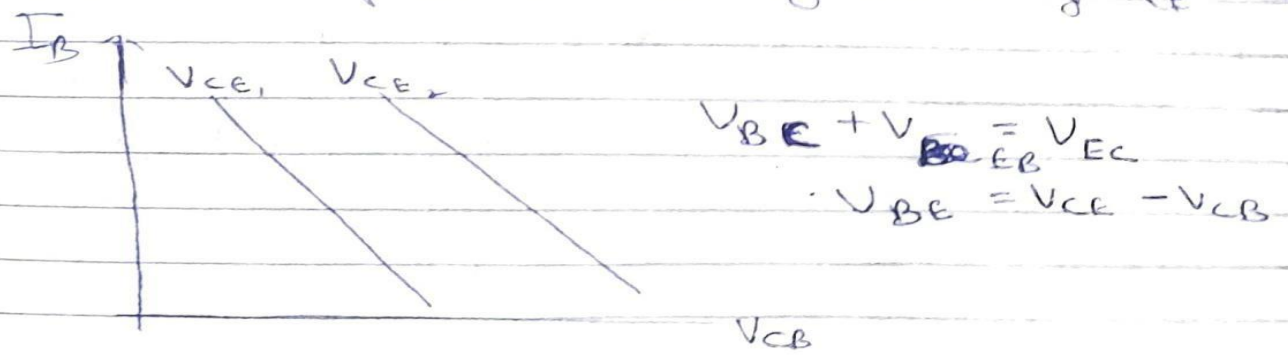
emitter emits e^- giving I_E at Base 5% of e^- are recombine giving I_B and remaining 95% of e^- move to collector giving I_C

$$\gamma = \frac{I_E}{I_B}$$

I/p O/p characteristics of CE configuration

I/p characteristics:-

It is a plot of I_B and V_{CE} by maintaining V_{CE} constant



O/p characteristics:-

It is a plot of I_E and V_{CE} by maintaining I_E constant



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Relationship w α , β and V

We know $I_E = I_B + I_C$

Dividing by I_C

$$\frac{I_E}{I_C} = \frac{I_B}{I_C} + \frac{I_C}{I_C}$$

$$\frac{1}{\alpha} = \frac{1}{\beta} + 1$$

$$\frac{1}{\alpha} = \frac{1 + \beta}{\beta}$$

$$\alpha = \frac{\beta}{1 + \beta}$$

Now $(1 + \beta)\alpha = \beta$

$$\alpha + \alpha\beta = \beta$$

$$\alpha = \beta - \alpha\beta$$

$$\alpha = \beta(1 - \alpha)$$

$$\beta = \frac{\alpha}{1 - \alpha}$$

Again

$$I_E = I_B + I_C$$

Dividing by I_B

$$\frac{I_E}{I_B} = 1 + \frac{I_C}{I_B}$$

$$V = 1 + \beta$$



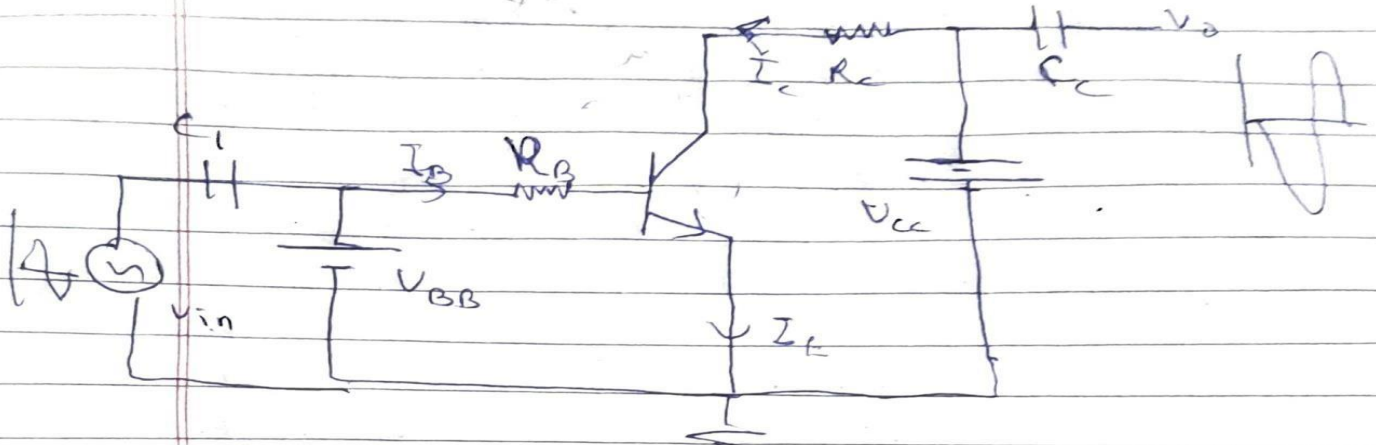
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$$r = 1 + \frac{\alpha}{1 - \alpha}$$

$$r = \frac{1 - \alpha + \alpha}{1 - \alpha} = \frac{1}{1 - \alpha}$$

BJT As an Amplifier



When no i/p voltage is applied

$$I_E = I_B + I_C \quad \text{--- (1)}$$

$$V_o = V_{CC} - I_E R_C \quad \text{--- (2)}$$

Now i/p ac voltage to be amplified to the i/p emitter base circuit. When the half cycle of i/p ac signal comes it supports the forward biasing of i/p emitter base circuit. Due to it emitter current \uparrow and collector current \uparrow from eq (1) so V_o become less (from eq (2)) i.e. more -ve during the half cycle.

When -ve half cycle of i/p ac voltage comes it opposes the forward biasing of i/p emitter base ckt. Due to it emitter current \downarrow and collector current \downarrow therefore from eq (2) V_o become more +ve.

Thus in CE amplifier ckt the i/p and o/p sig voltage are in opposite phase.

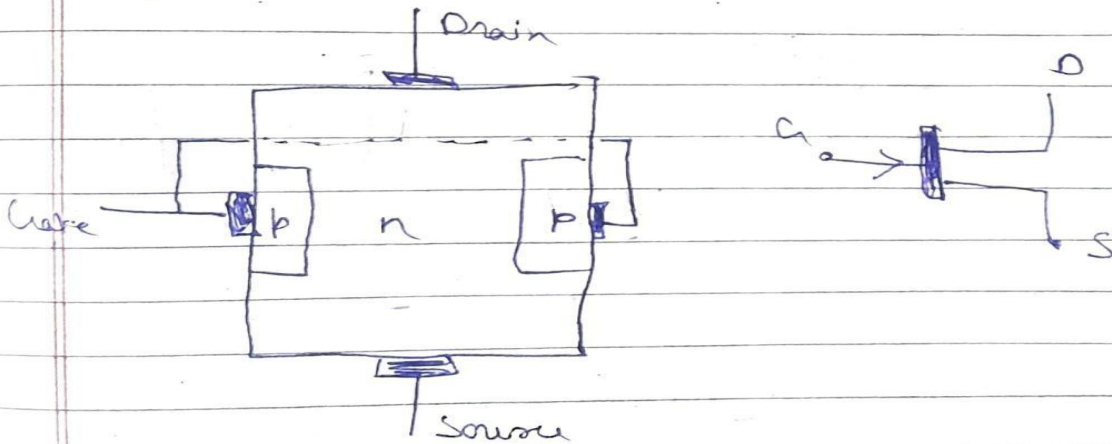
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Field-effect Transistor (FET)

FET is a three terminal (namely drain, source and gate) s/c device in which current conduction is by only one type of majority carriers (e^- in n-channel and holes in p-channel). It is also called unipolar Transistor.

n-Channel JFET (Junction Field effect Transistor)

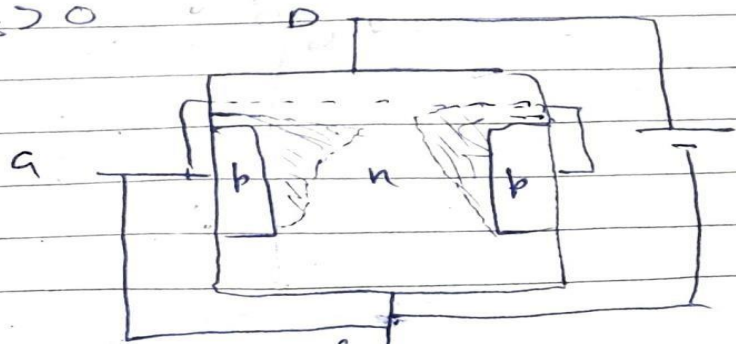
n channel JFET has n type base. On both side of base two heavily doped p regions are formed so two p-n junction is formed which are internally connected by a gate terminal. Other two terminal are drain and source.



Working of n-Channel JFET

Case I

$$V_{GS} = 0 \quad V_{DS} > 0$$



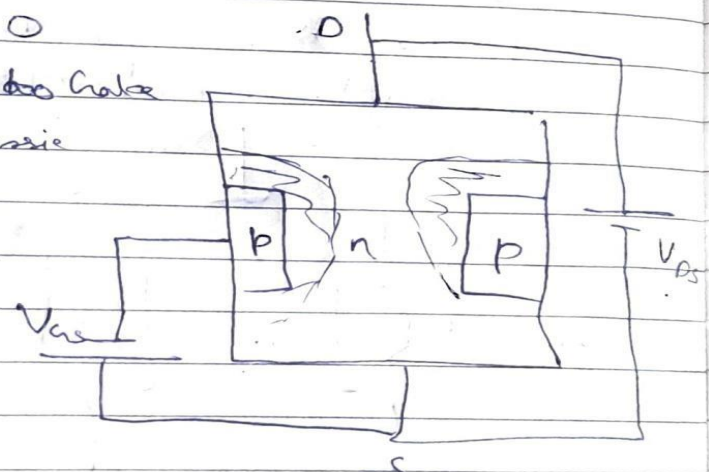


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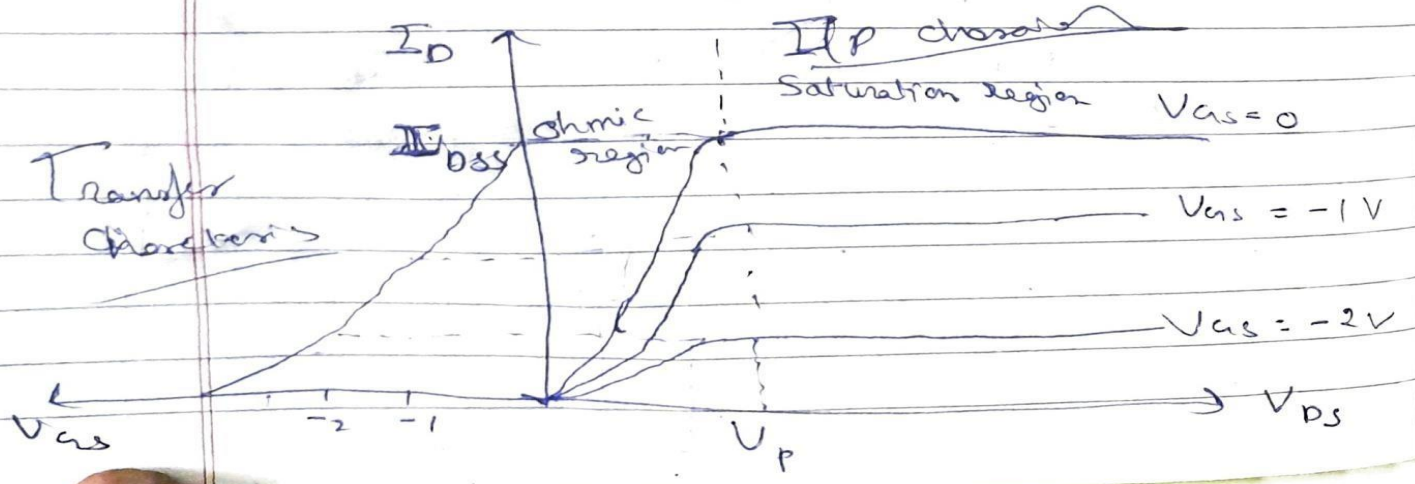
In JFET structure the channel is uniformly doped and if current flowing from drain to source, the voltage at upper part of the channel is higher than the lower part. So if $V_{GS} > 0$ and $V_{DS} = 0$ both pn junction are reverse biased. This reverse bias voltage is not uniform and decrease as we move downwards. So a non uniform depletion region is formed at junction. At certain value of V_{DS} width of depletion layer become max. and drain current become constant. It is called pinch off voltage (V_P)

Case II $V_{GS} > 0$ $V_{DS} < 0$

In this case source to gate junction become reverse biased so pinch off voltage get become Case I



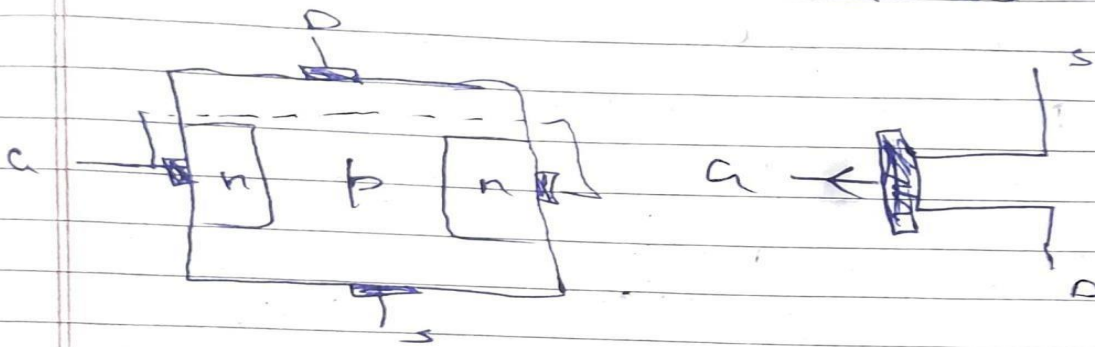
Transfer characteristics of the JFET



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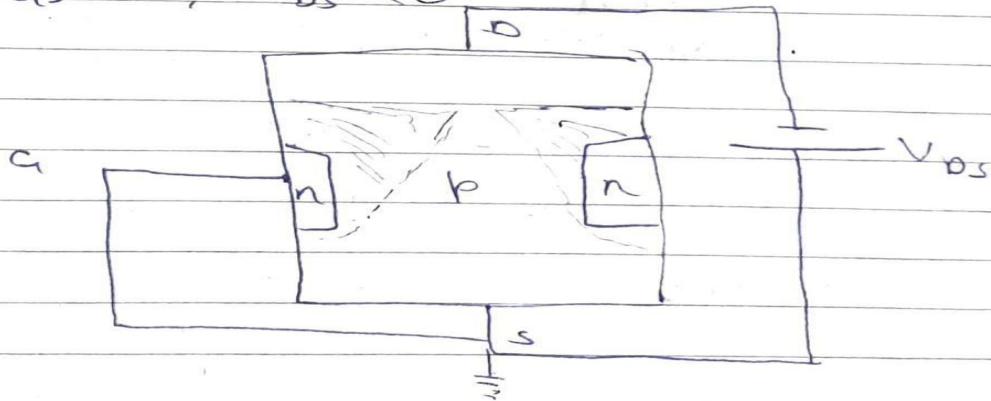
P channel JFET

In p channel JFET have p type base on both side of base two heavily doped ~~n~~ n regions are formed so two pn junction is formed which are internally connected by gate and other two are drain and source



Working of p channel JFET

(Case I) $V_{GS} = 0$, $V_{DS} < 0$



In JFET structure the channel is uniformly doped. If current flowing from drain to source voltage of upper part of channel is lower than the lower part. So if $V_{DS} < 0$ and $V_{GS} = 0$ both pn junction are reverse biased. This reverse bias voltage is not uniform and \downarrow as we move downwards so a non uniform depletion region is formed at junctions.

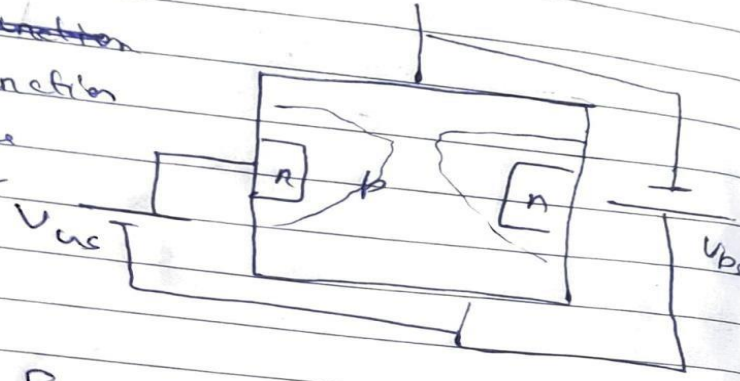


At certain value V_{DS} width of depletion region becomes max. and drain current become constant

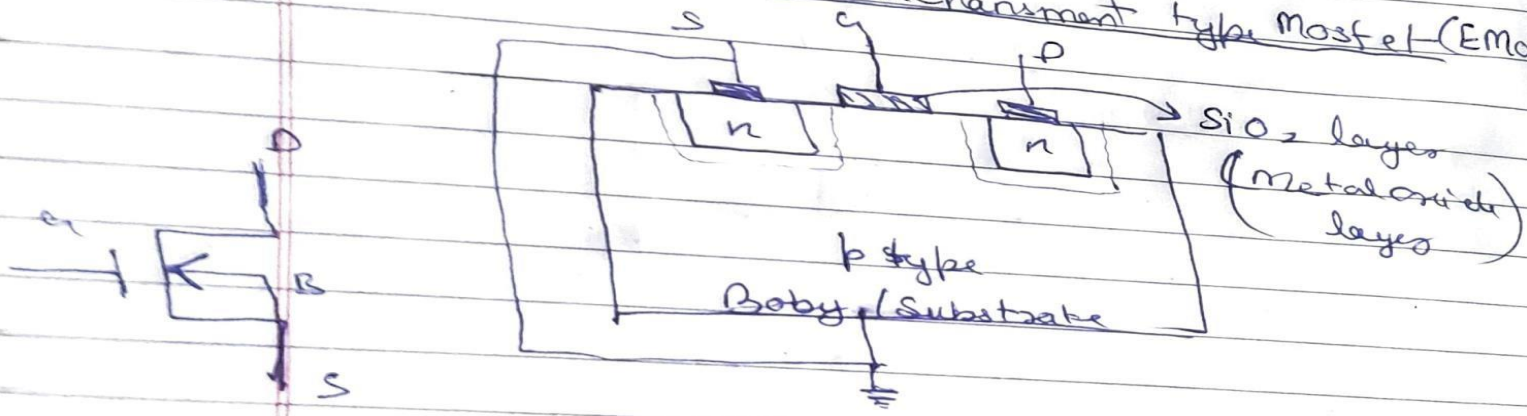
Case II)

$V_{GS} > 0$ $V_{DS} < 0$

In this case ~~pn junction~~ Source and Gate junction become more reverse biased so V_p get before case I.



n channel Enhancement type Mosfet (EMOSFET)



n channel EMOSFET consist of p type body with two heavily doped n type material which drain and source. The gate terminal is separated by SiO_2 layer

Working of nchannel EMOSFET

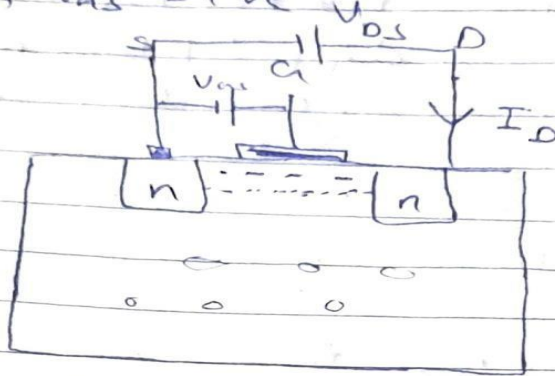
Case I)

When $V_{GS} = +ve$ and $V_{DS} = 0$ or $V_{DS} = -ve$ If V_{DS} is \uparrow then no current will flow because there is no channel i.e. $I_D = 0$

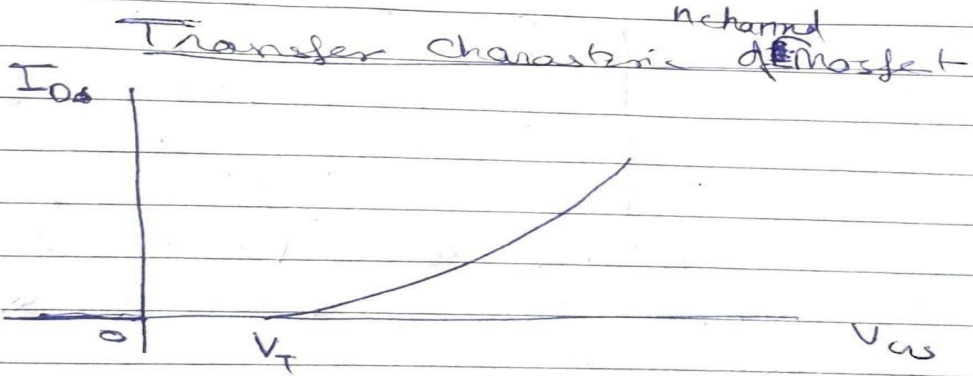
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Case II

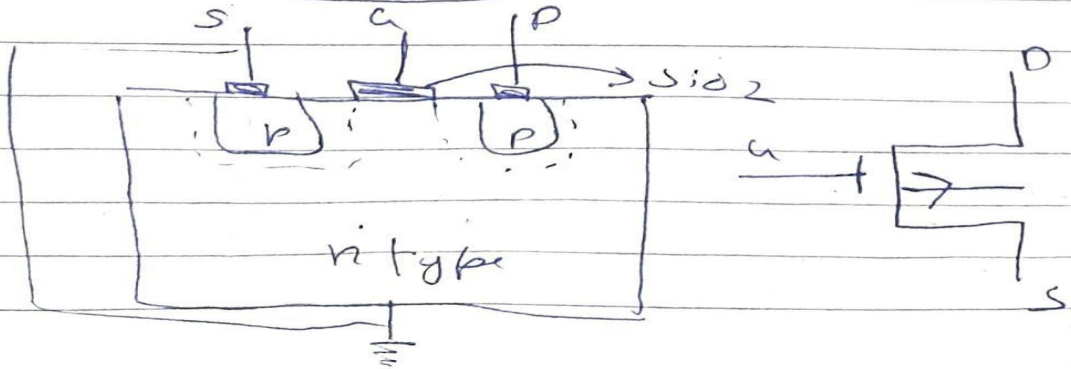
$V_{DS} = +ve, V_{GS} = +ve$



If the voltage is applied at gate then e^- in p-type moves towards the gate and holes moves away from the gate. At that voltage channel is formed is called Threshold voltage (V_T). If V_{GS} is further \uparrow ed then I_D continuously \uparrow es.



P channel E MOSFET





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p channel E MOSFET consist of n type body with two heavily doped p type material which is drain and source. The gate terminal is separated by SiO_2 layer.

Working of P channel E MOSFET

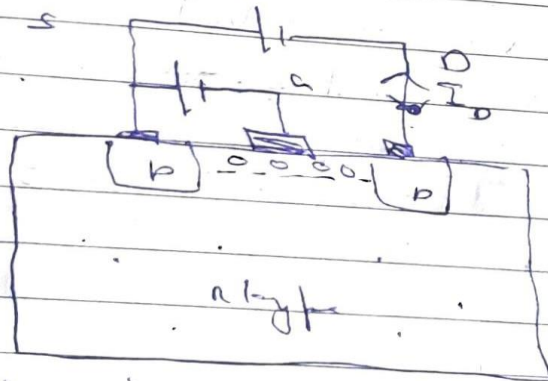
Case I

$V_{DS} = -ve$ or $+ve$ $V_{GS} = 0$

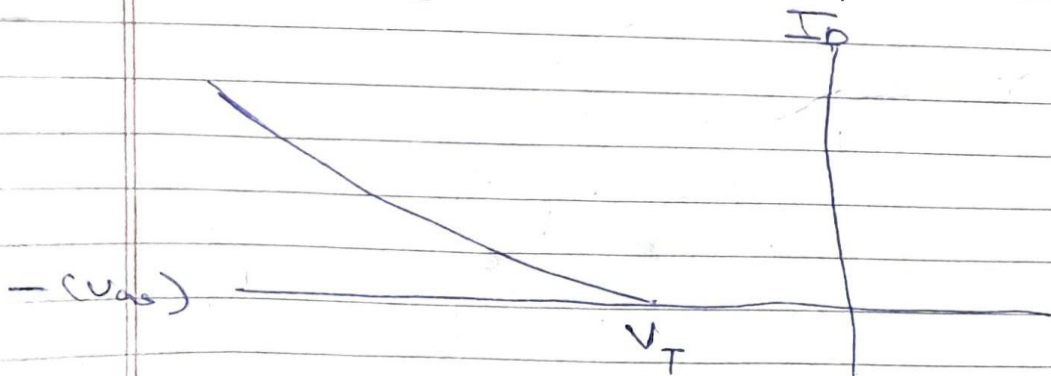
If V_{GS} is 0 there is no current flow because there is no channel is formed.

Case II

$V_{DS} = -ve$ or $V_{GS} = -ve$



If $-ve$ voltage is applied to the gate then holes in the n type move towards the gate and e^- move away from the gate.



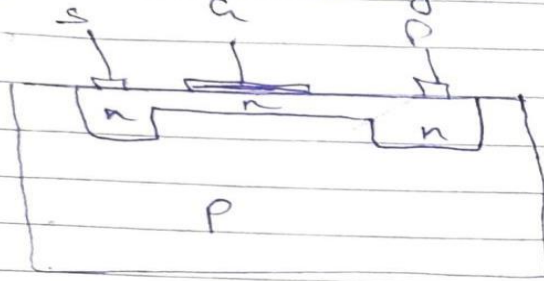


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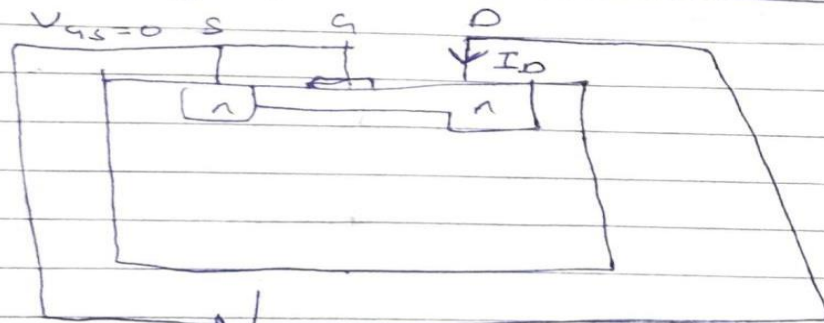
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n-channel Depletion MOSFET (DMOSFET)

n-channel DMOSFET have p-type base. Then two n regions are formed. A thin layer of SiO_2 is deposited drain and source are connected with metallic contact. An channel is formed b/w two n regions. ~~Gate~~ so I_g is 0. Gate is insulated from n-channel by SiO_2 layer



Working of nchannel DMOSFET



Case I $V_{gs} = +V$ $V_{ds} = 0$

When V_{ds} is \uparrow more and more e^- move from S to D so current I_d . A condition comes when current become constant. This condition is called pinch off condition. The value of V_{ds} which established this condition is called pinch off voltage (V_p). After V_p current become constant.

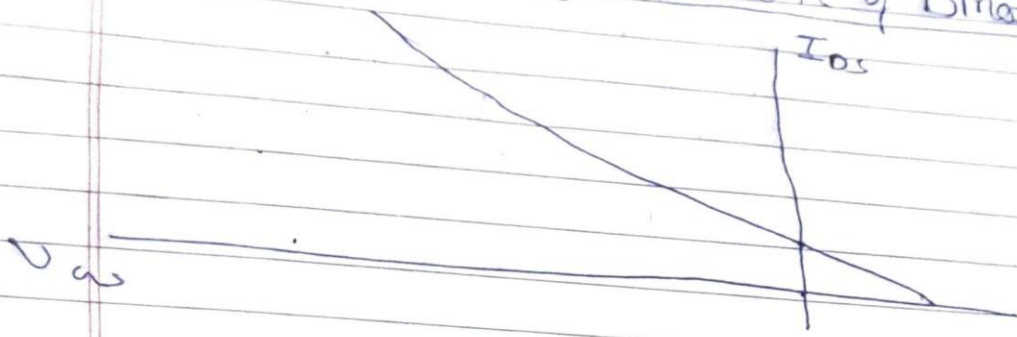


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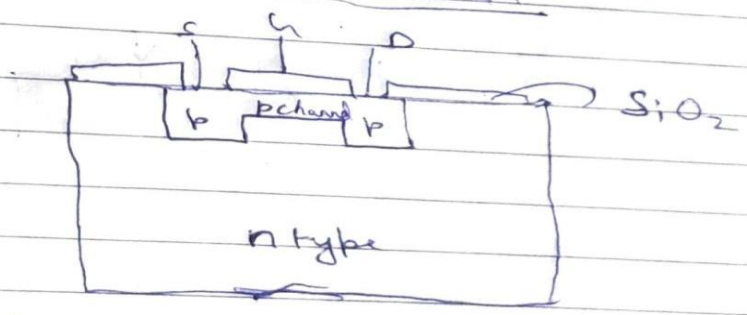
Case II

$V_{GS} = +ve$ and $V_{DS} = -ve$
If V_{GS} is \uparrow ed then holes in p-type move towards the channel so recombination process occurs in channel so pinch off condition comes earlier

Transfer characteristic of DMOSFET



P Channel DMOSFET

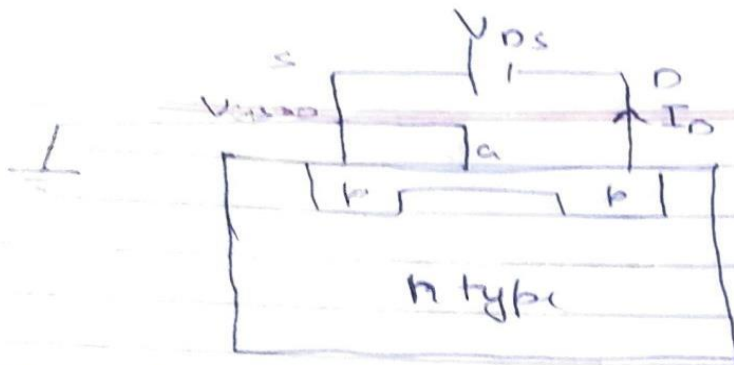


P channel DMOSFET have n type body with two p type region are formed. Drain and source are connected by metallic contact and gate separated by SiO_2 by. A channel is formed b/w two regions.

Working of P channel DMOSFET

Case I

$V_{GS} = 0$ $V_{DS} = -ve$



when $V_{ds} \uparrow$ more and more holes move from S to D
So current I_{ds} . A condition comes when current becomes
constant. This condition is called pinch-off condition.
At that condition V_{ds} called Pinch-off voltage (V_p)
After V_p current becomes constant.

Case II) $V_{gs} = -V_c$ and $V_{ds} = +V_c$
If V_{gs} is \uparrow then e^- in n type move towards the
channel so recombination process occurs in channel
so pinch-off condition comes earlier.